

**ALIGNMENT SYSTEM AND METHOD USING BRIGHT SPOT
AND BOX STRUCTURE**

ABSTRACT OF THE DISCLOSURE

5 There is provided a method for aligning a semiconductor wafer and a mask. A semiconductor wafer is provided having an alignment mark formed thereon. A mask is provided having a pattern formed thereon. The mask is illuminated so as to create a bright spot thereon by a $0-\pi$ phase conflict. The alignment mark is aligned with the bright spot, so as to align the semiconductor wafer with the mask. Preferably, the method includes the step of creating the alignment mark on the semiconductor wafer in a form of a frame. Moreover, preferably, the creating step

10 includes the step of creating the frame to minimize an impact of film stack variations.

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